

Please amend the abstract as follows:

#### ABSTRACT OF THE DISCLOSURE

Photomask repair and fabrication with use of direct-write nanolithography, including use of scanning probe microscopic tips for deposition of ink materials including sol-gel and metallic inks. Additive methods can be combined with ~~subtractive~~ subtractive methods. Holes can be filled with nanostructures. ~~Height~~ Heights of the ~~nanostucture~~ nanostructures filling the ~~hole~~ holes can be controlled without losing control of the lateral dimensions of the ~~nanostucture~~ nanostructures. Chrome-on-Glass masks can be used and fabricated, as well as phase shifting masks (PSMs) and more advanced masks including masks for nanoimprint nanolithography.